

FORMING METAL MASK ON SILICON SUBSTRATE STEP 1 FORMING AND PATTERNING RESIST FILM STEP 2 PATTERNING METAL MASK STEP 3 REMOVING RESIST FILM → STEP 4 CRYSTAL-ANISOTROPY ETCHING SILICON SUBSTRATE (FORMING A RECESS OF A SUBSTANTIALLY TRUNCATED QUADRANGULAR PYRAMID) STEP 5 REMOVING METAL MASK \sim STEP 6 FORMING SEPARATION LAYER (METAL THIN FILM) → STEP 7 FORMING AND PATTERNING INSULATION LAYER - Step 8 FORMING METAL LAYER STEP 9 FORMING AND PATTERNING RESIST FILM → STEP 10 ✓ STEP 11 ETCHING METAL LAYER ✓ STEP 12 REMOVING RESIST FILM WET-ETCHING SEPARATION LAYER (PEELING MEMBER FORMED OF INSULATION LAYER AND METAL LAYER FROM SILICON SUBSTRATE) STEP 13

FIG. 2

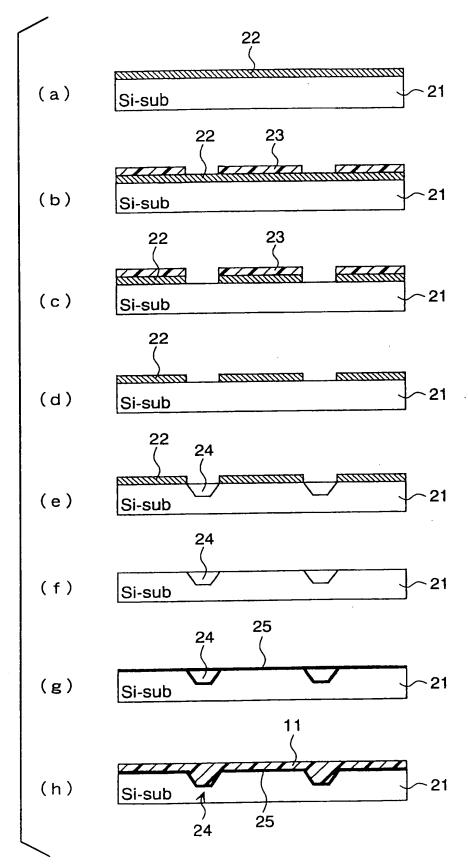
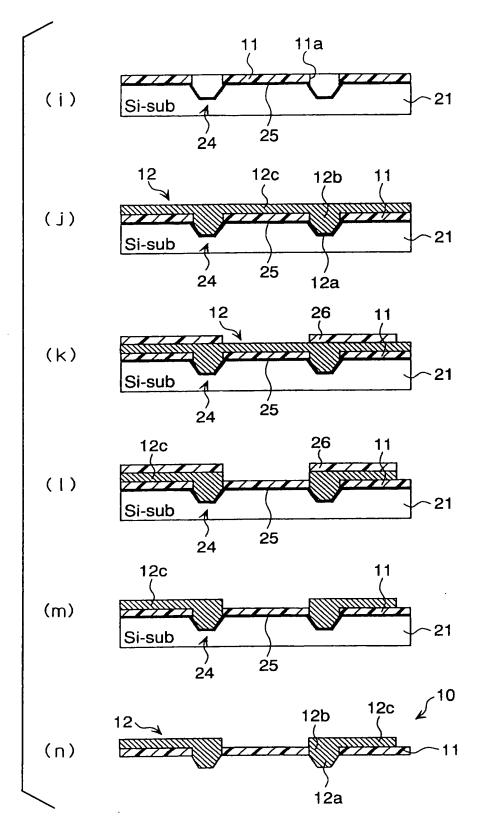


FIG. 3



F1G. 4

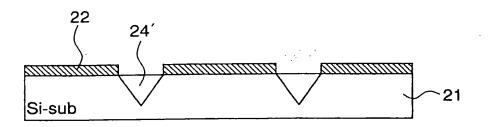


FIG. 5

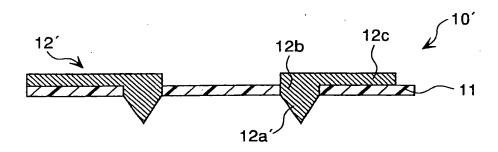


FIG. 6

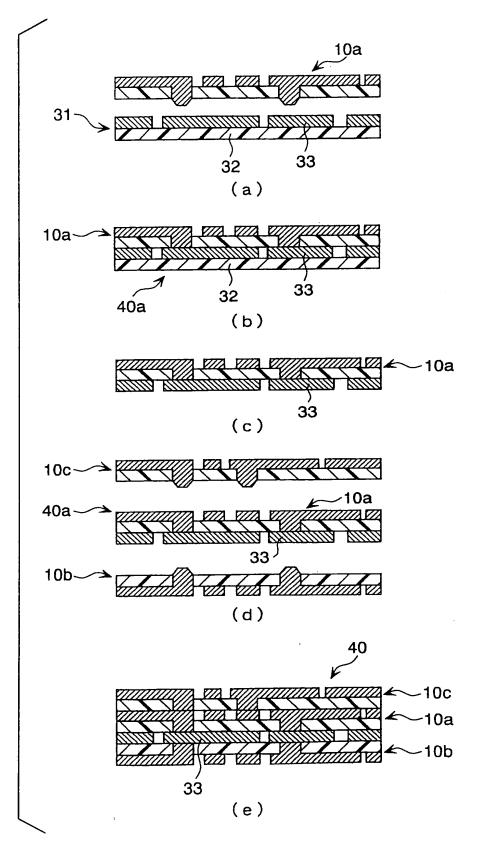


FIG.7